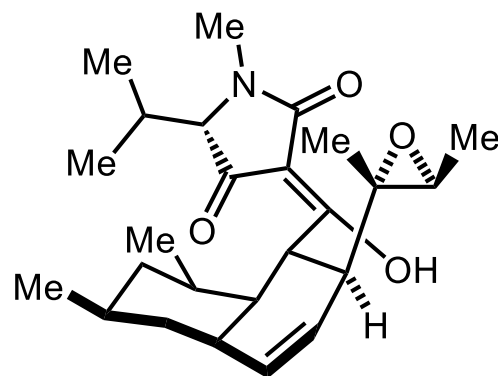


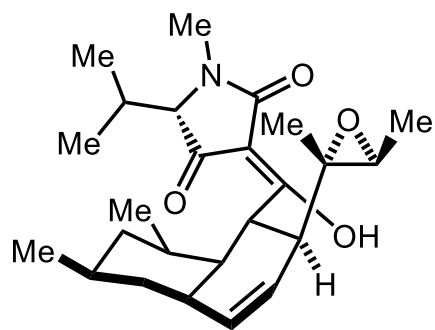
Total Synthesis of Diverse Tetramic Acid Bearing *cis*-Decalin Natural Products

Haoran Dong,^[a] ‡ Dachao Hu,^[b] ‡ Benke Hong,^[a] ‡ Jin Wang,^[a] Xiaoguang Lei^{*[a,c]}

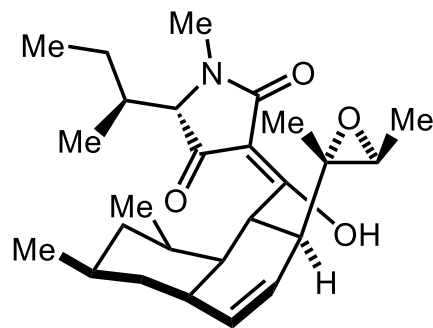


vermispurin (1)

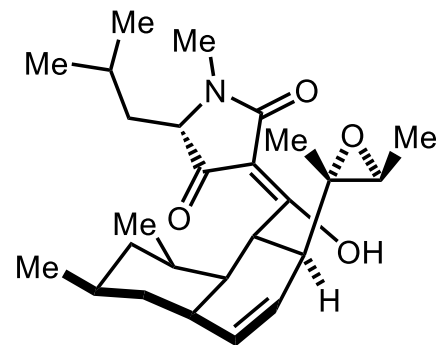
(A)



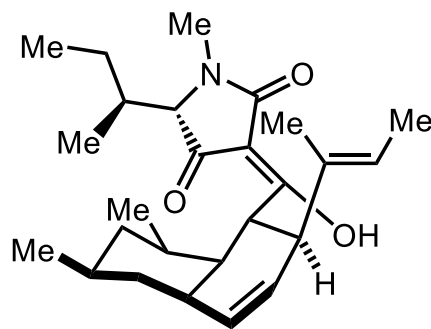
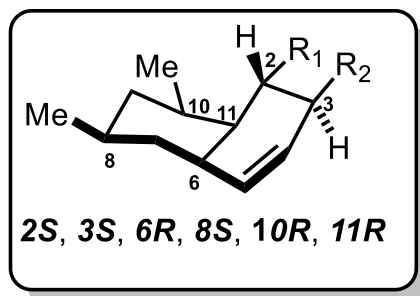
vermisporin (1)



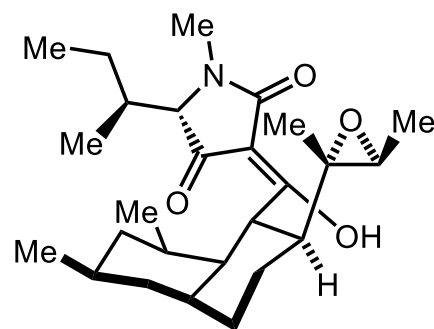
PF1052/AB4015-A (2)



AB4015-L (3)



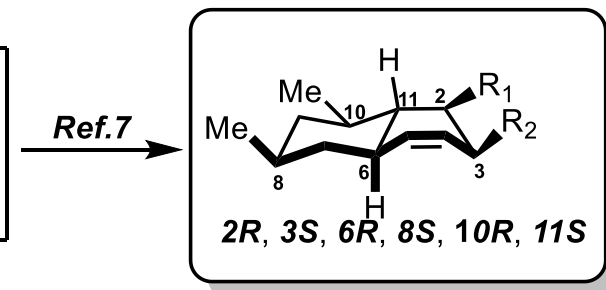
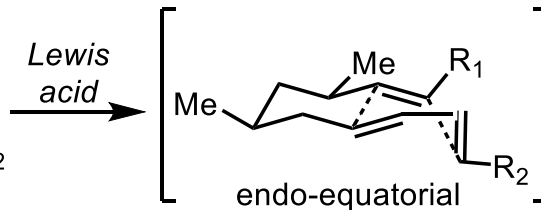
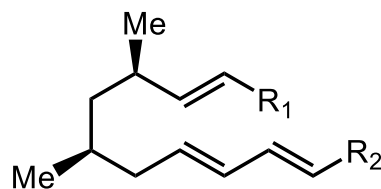
AB4015-B (4)



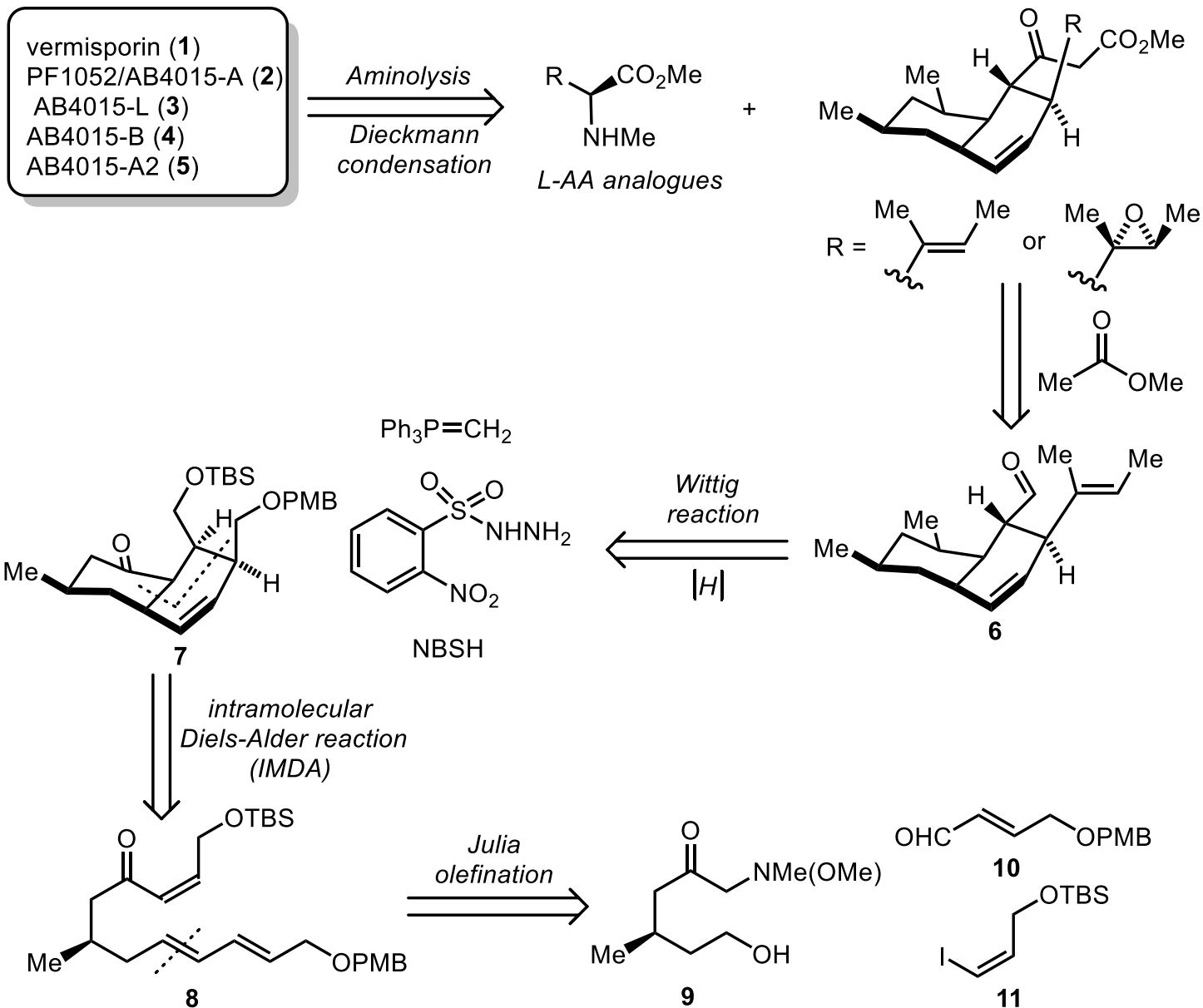
AB4015-A2 (5)

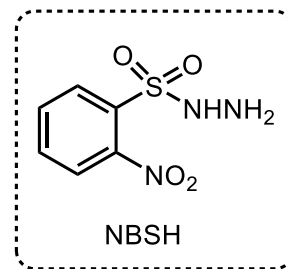
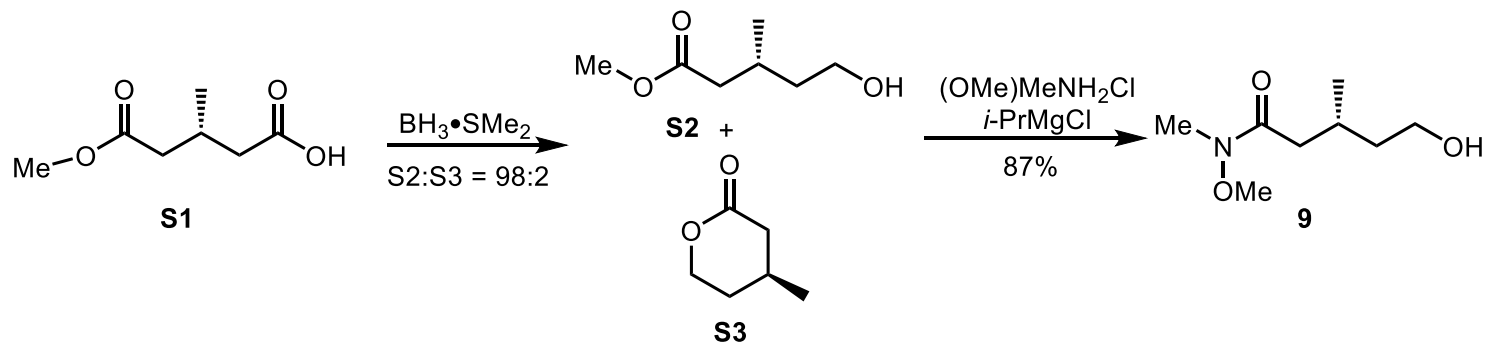
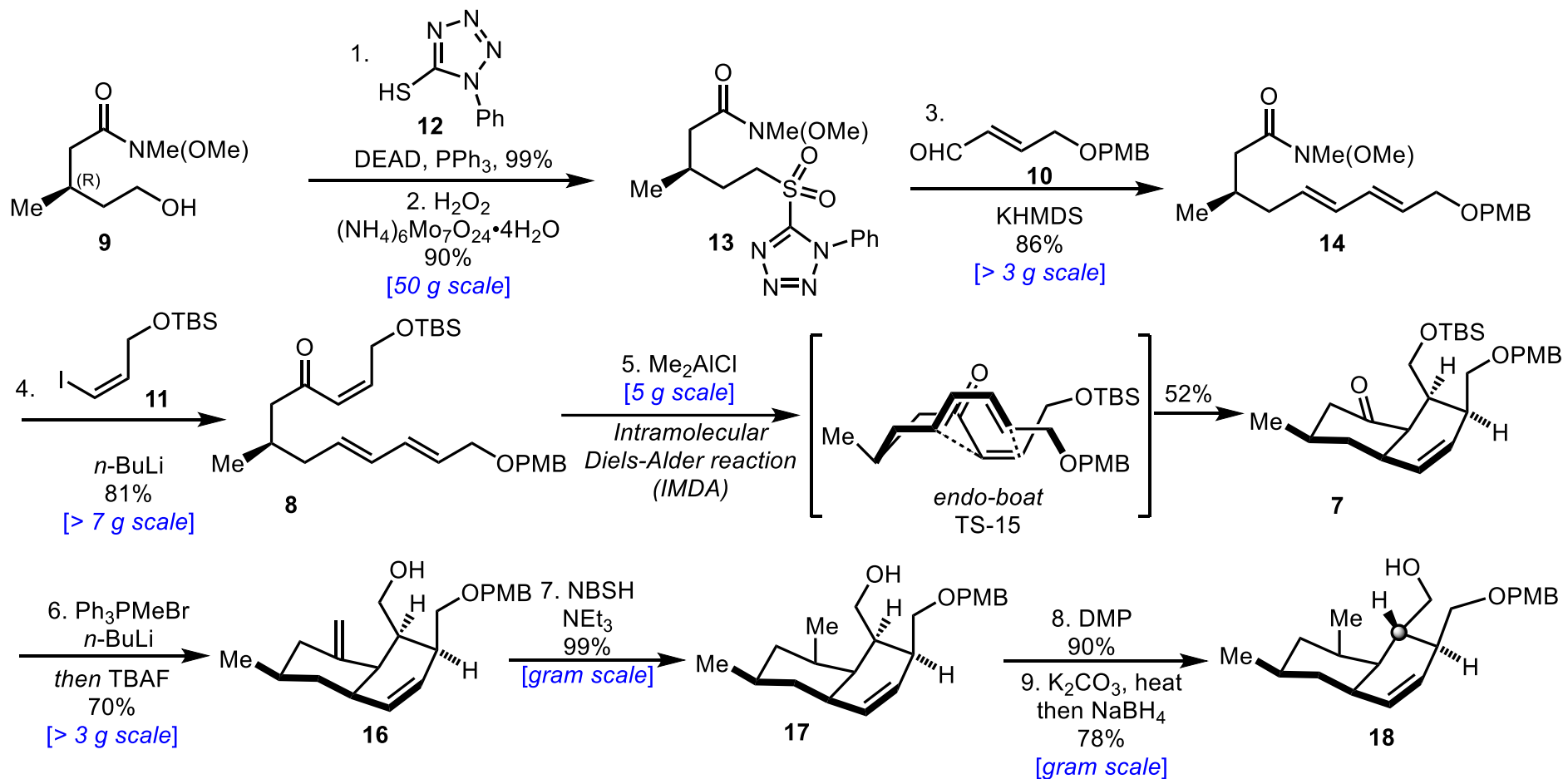
Biosynthesis

(B)



Retrosynthetic analysis

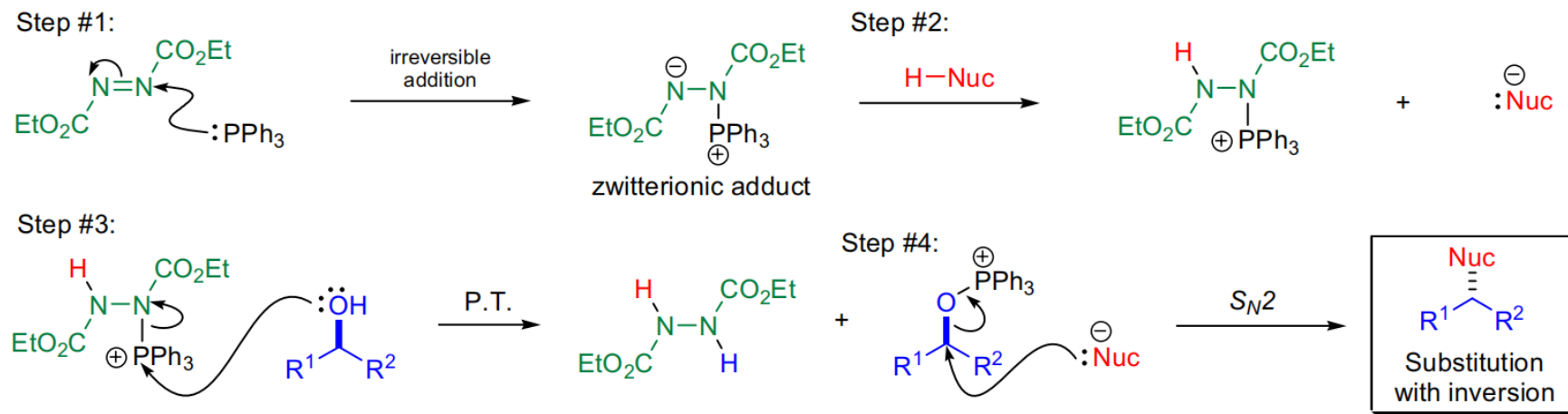




MITSUNOBU REACTION

(References are on page 632)

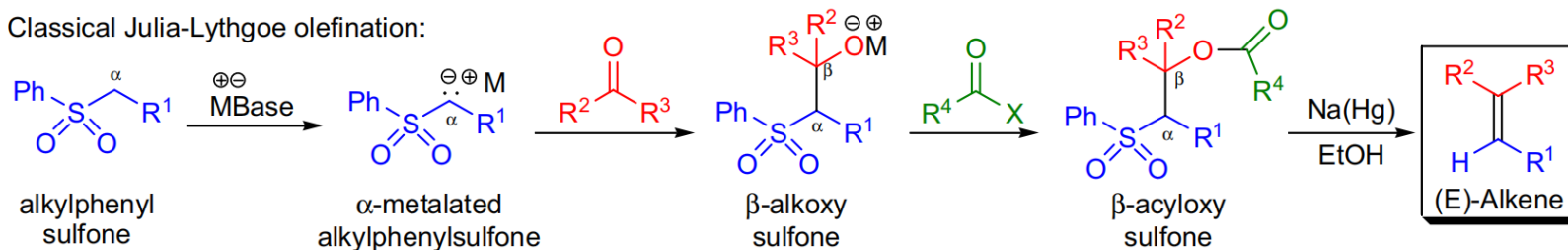
Mechanism: ²⁵⁻⁴⁵



JULIA-LYTHGOE OLEFINATION

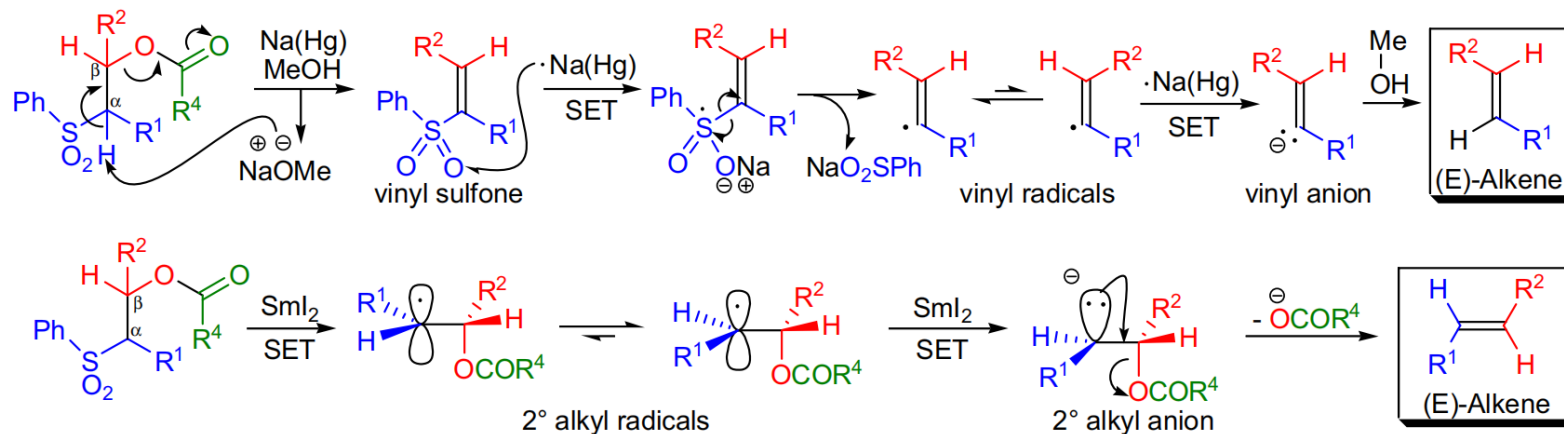
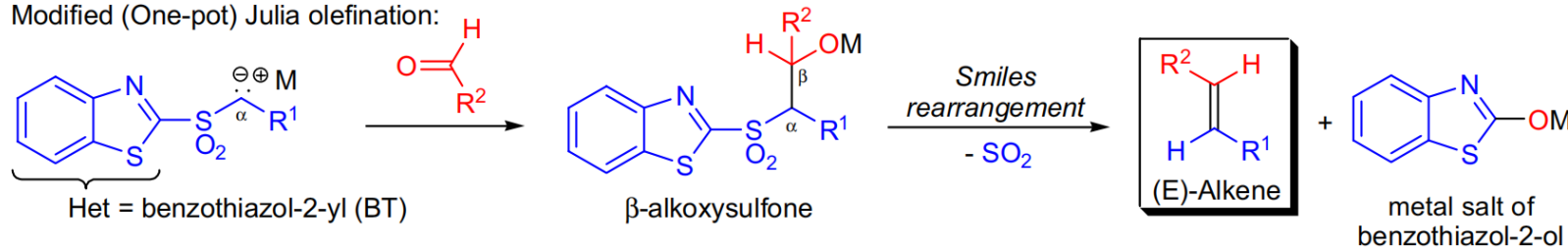
(References are on page 610)

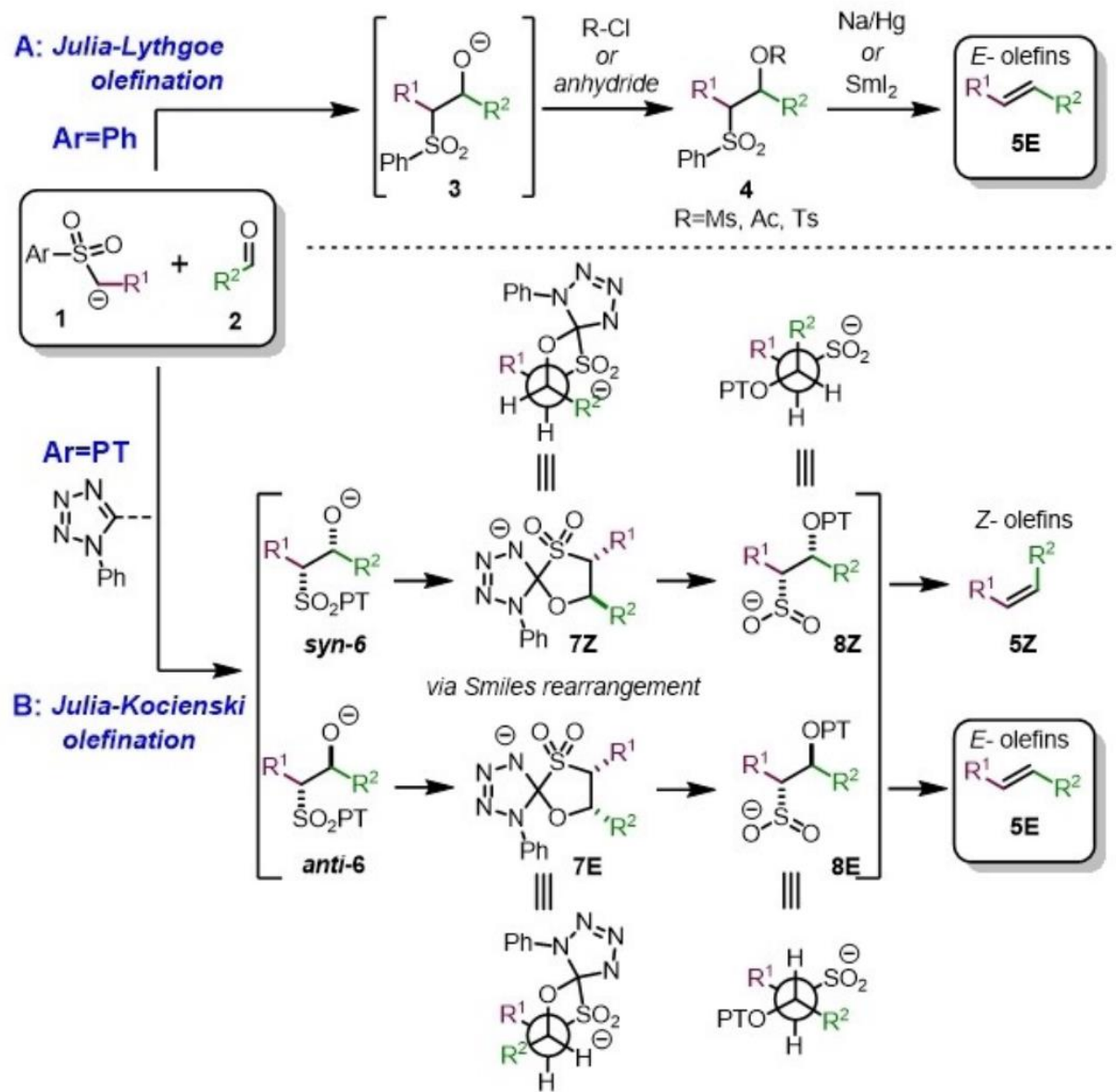
Classical Julia-Lythgoe olefination:



R¹ = H, alkyl, aryl; R², R³ = H, alkyl, aryl, alkenyl; R⁴ = alkyl, aryl; X = Cl, Br, OCOR

Modified (One-pot) Julia olefination:





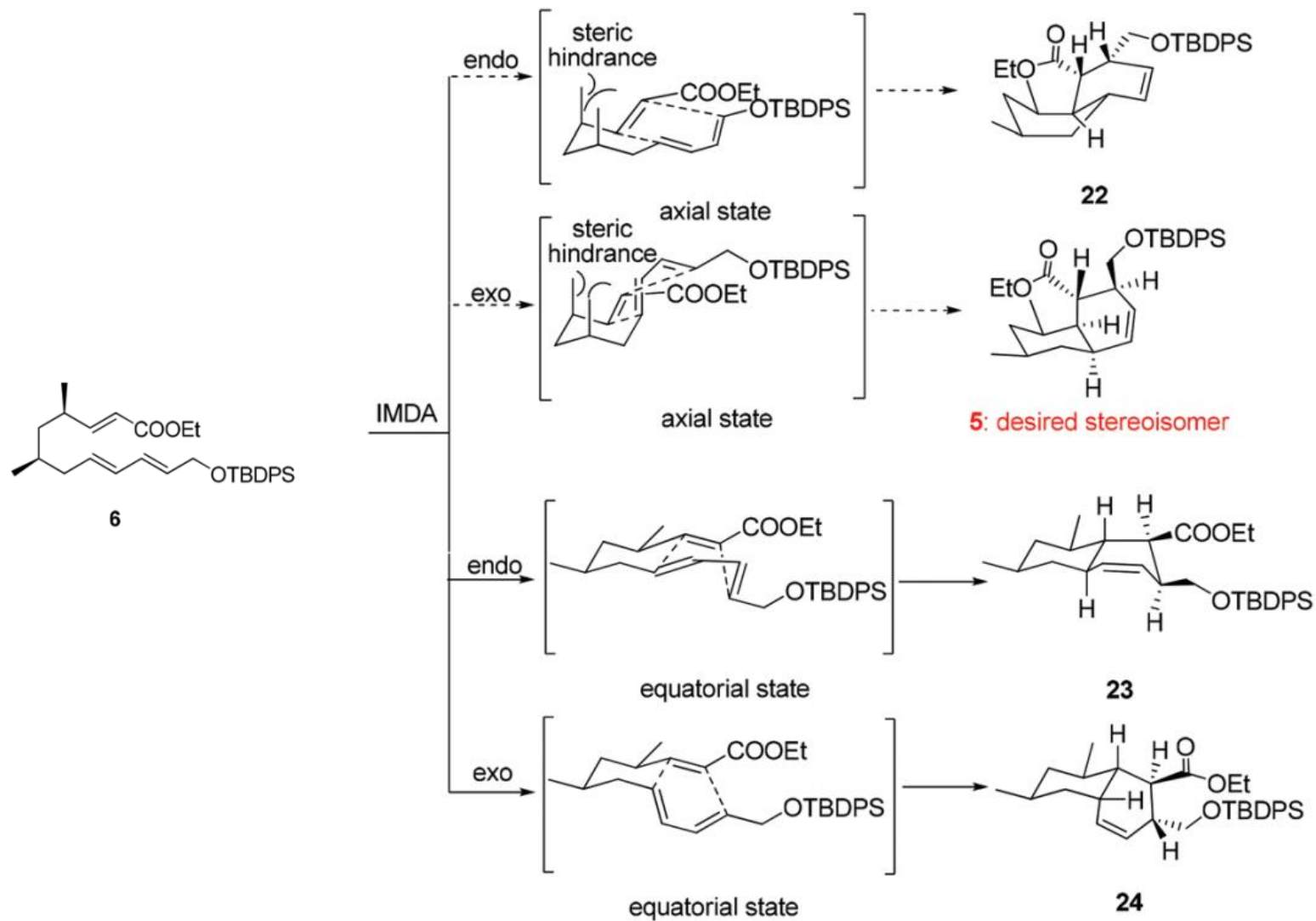
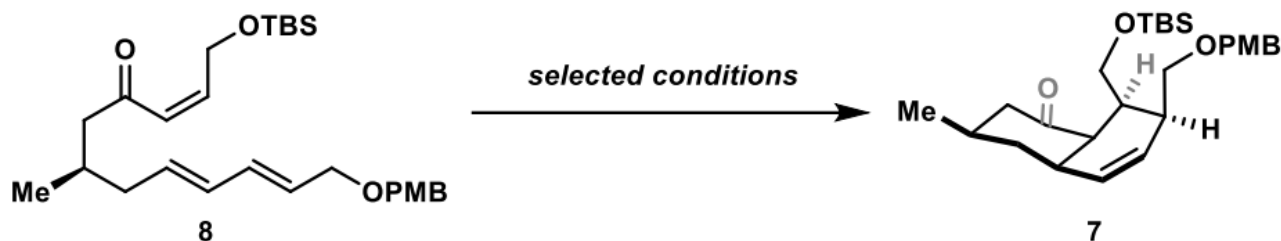
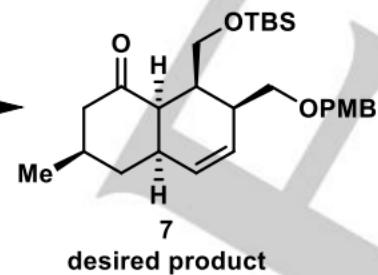
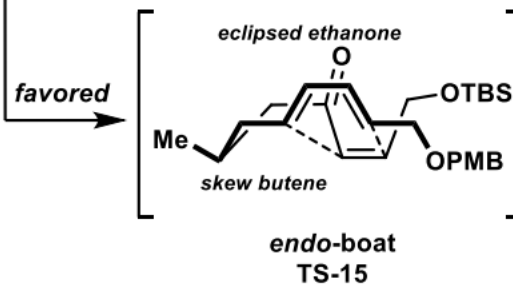
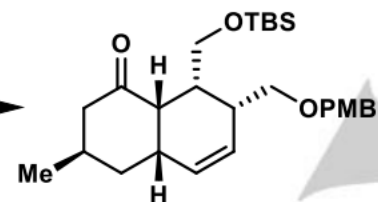
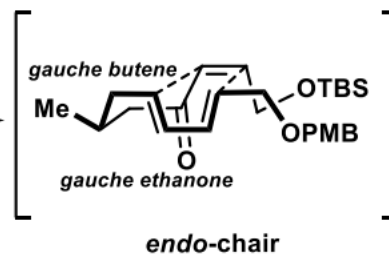
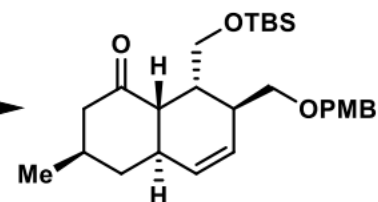
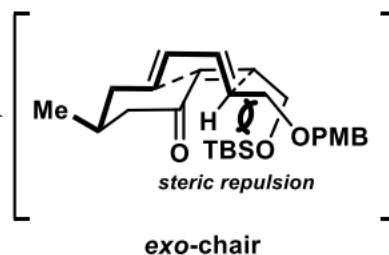
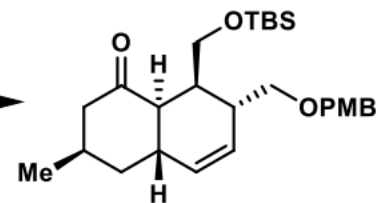
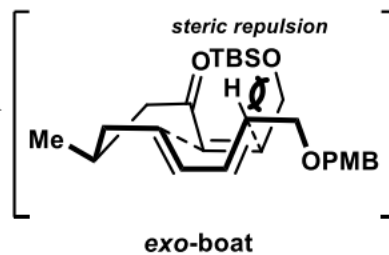


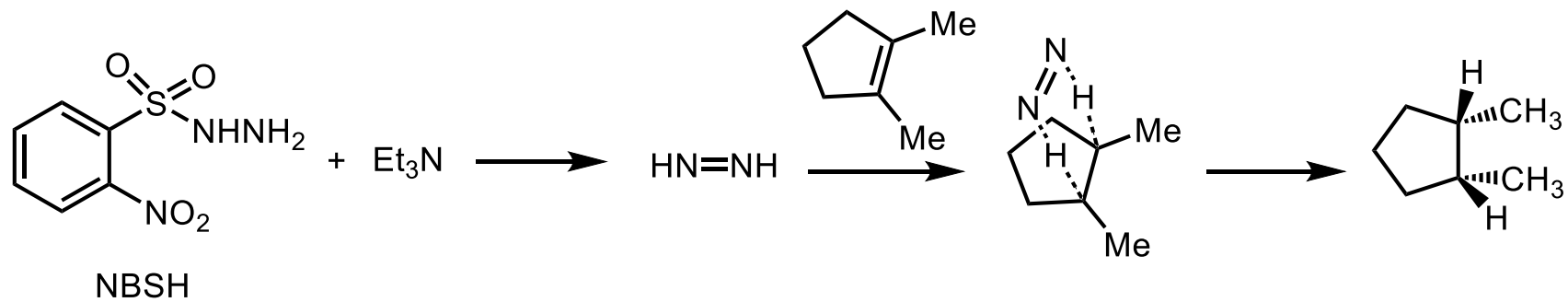
Table S1. Condition screening of IMDA reaction



Entry	Condition	Solvent	Temp.	Isolated yield of 7
1	neat	---	rt.	< 10%
2	silica gel	DCM	rt.	< 10%
3	---	PhCl	160 °C	20%
4	Me ₂ AlCl (0.5 eq.)	DCM	0 °C	52%
5	BF ₃ ·OEt ₂ (0.5 eq.)	DCM	-78 °C to -30 °C	24%
6	EtAlCl ₂ (0.5 eq.)	DCM	0 °C	41%
7	SnCl ₄ (0.5 eq.)	DCM	-78 °C to -30 °C	26%

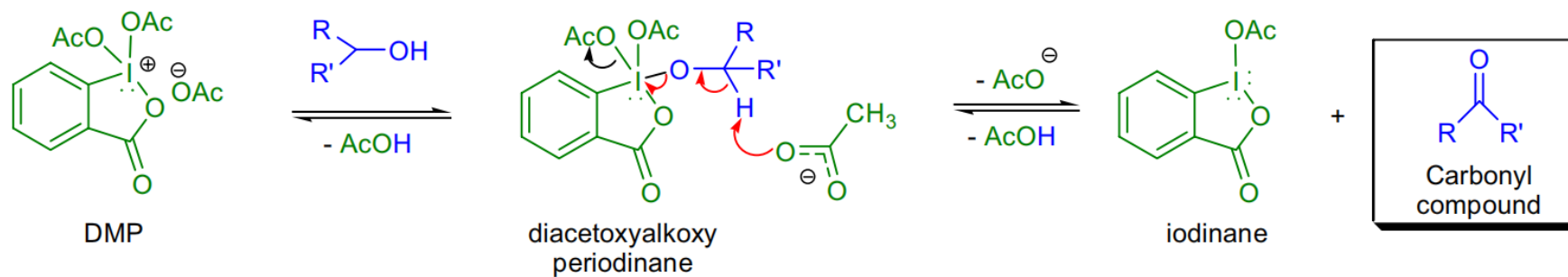
8 *IMDA*

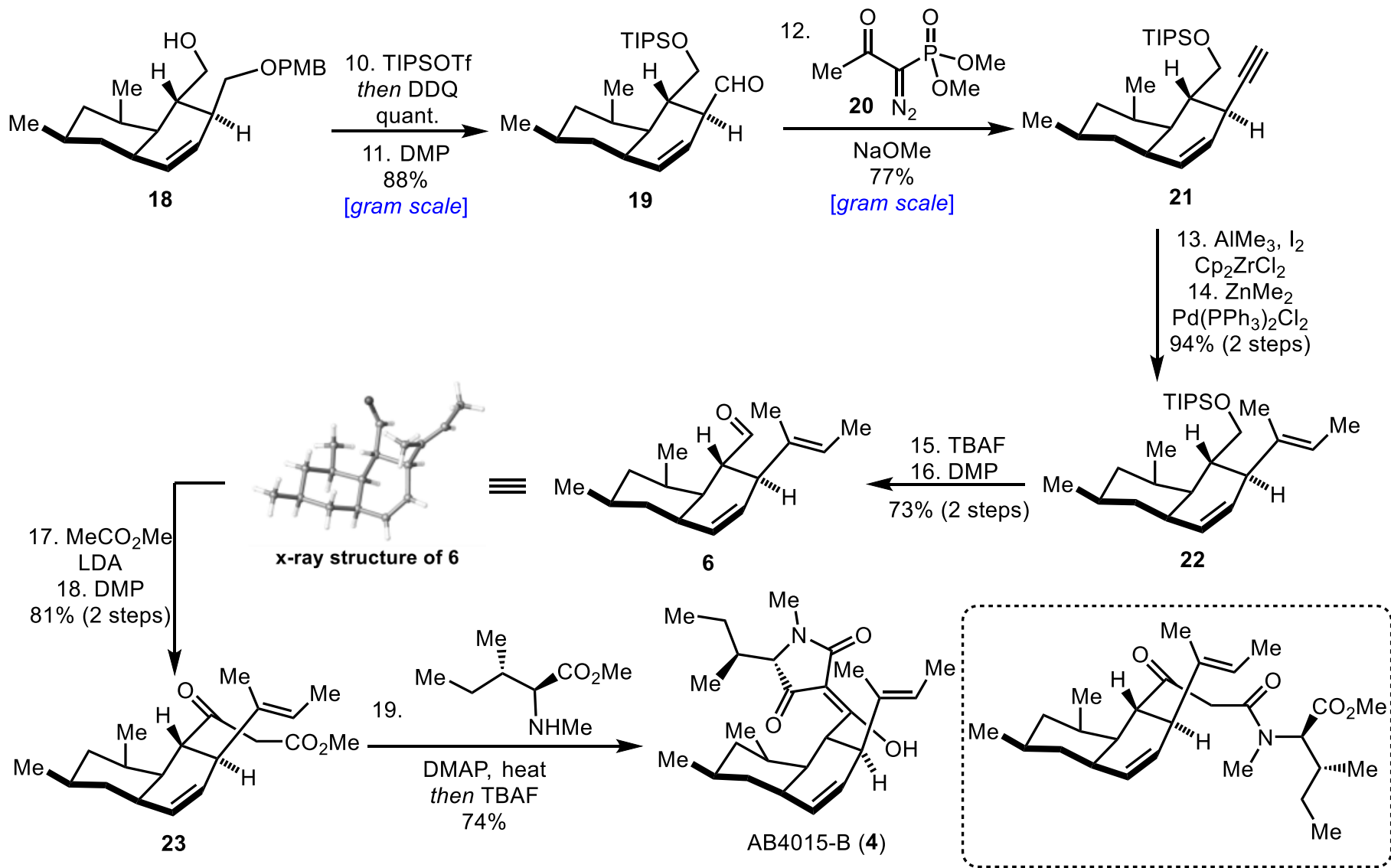




DESS-MARTIN OXIDATION

(References are on page 574)

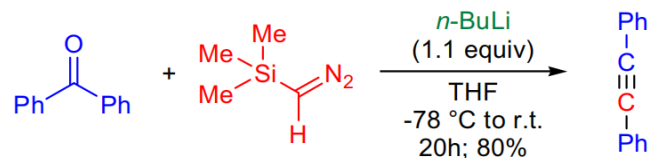




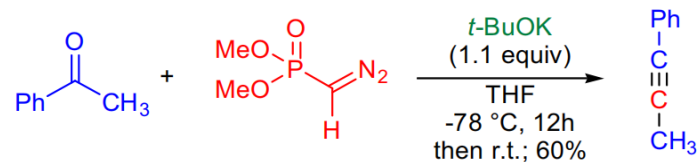
SEYFERTH-GILBERT HOMOLOGATION

(References are on page 672)

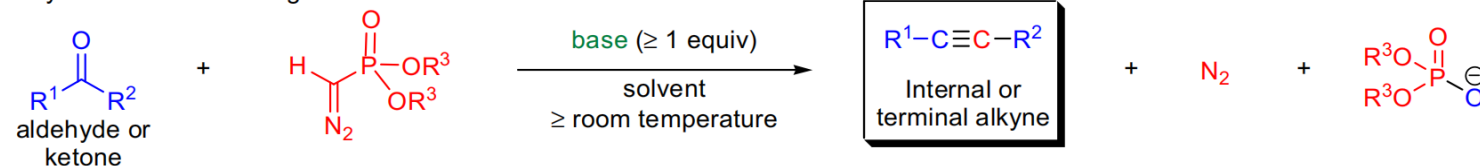
Colvin & Hamill (1973):



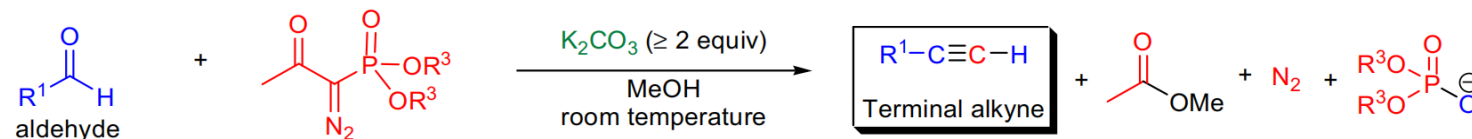
Gilbert & Weerasooriya (1979):



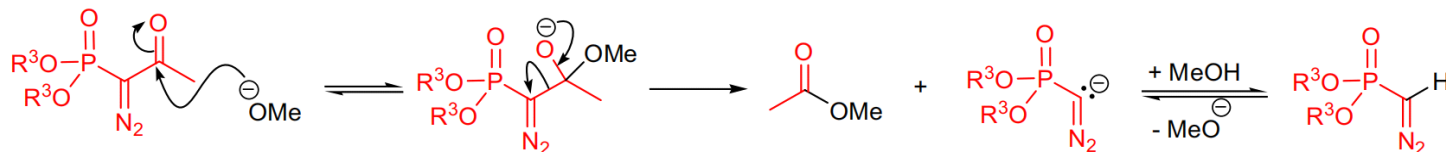
Seyferth-Gilbert homologation:



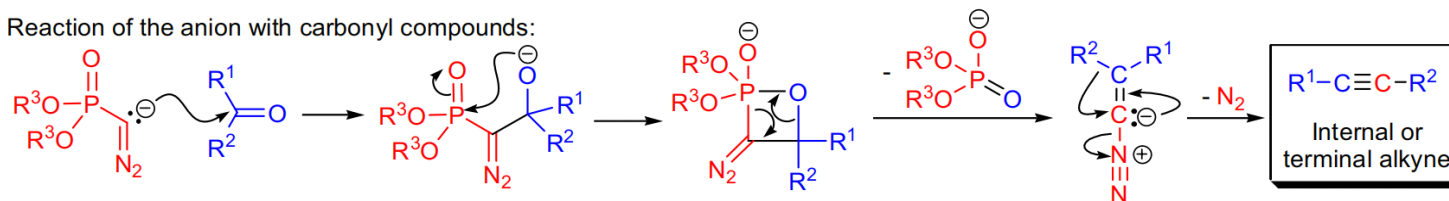
Modification for the synthesis of terminal alkynes (Ohira & Bestmann):

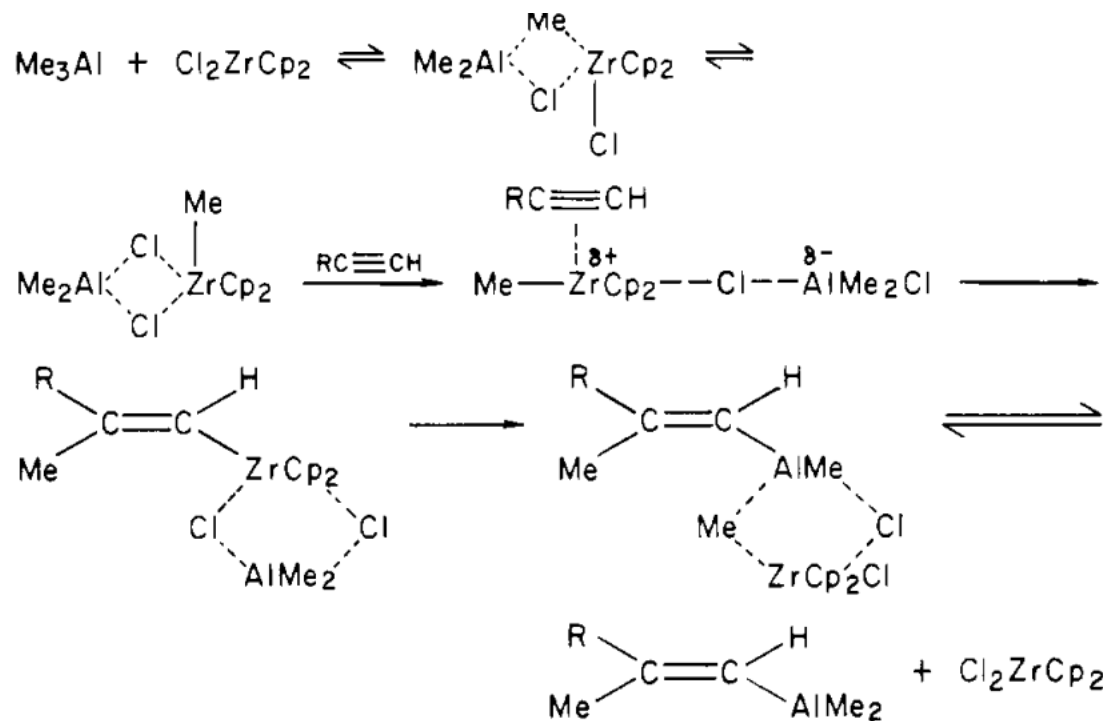
 R^1 = alkyl, aryl, heteroaryl; R^2 = H, aryl, heteroaryl; R^3 = Me, Et; base: $n\text{-BuLi}$, $\text{KO-}t\text{Bu}$

Formation of the dialkylphosphonodiazomethane from dialkyl-1-diazo-2-oxopropylphosphonate:

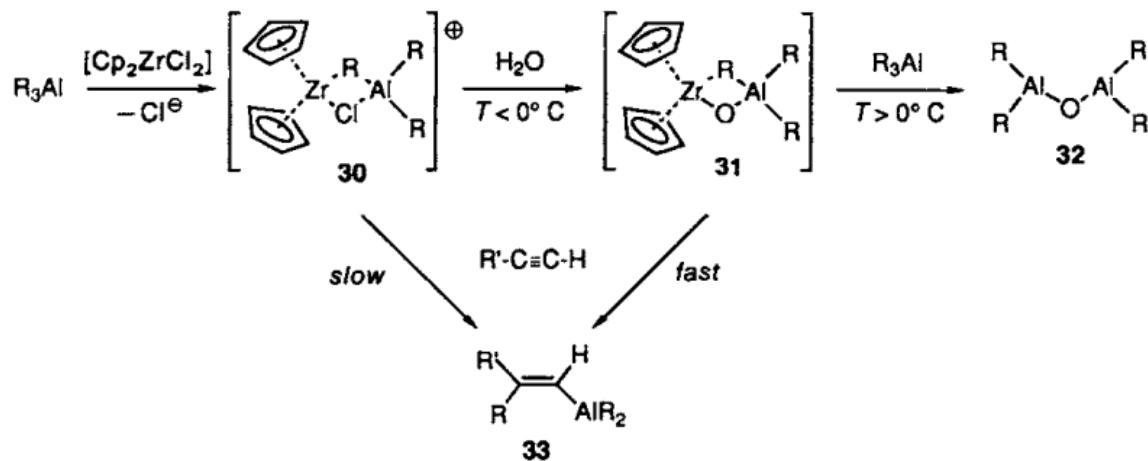


Reaction of the anion with carbonyl compounds:





J. Am. Chem. soc., **1985**, 107, 6639.



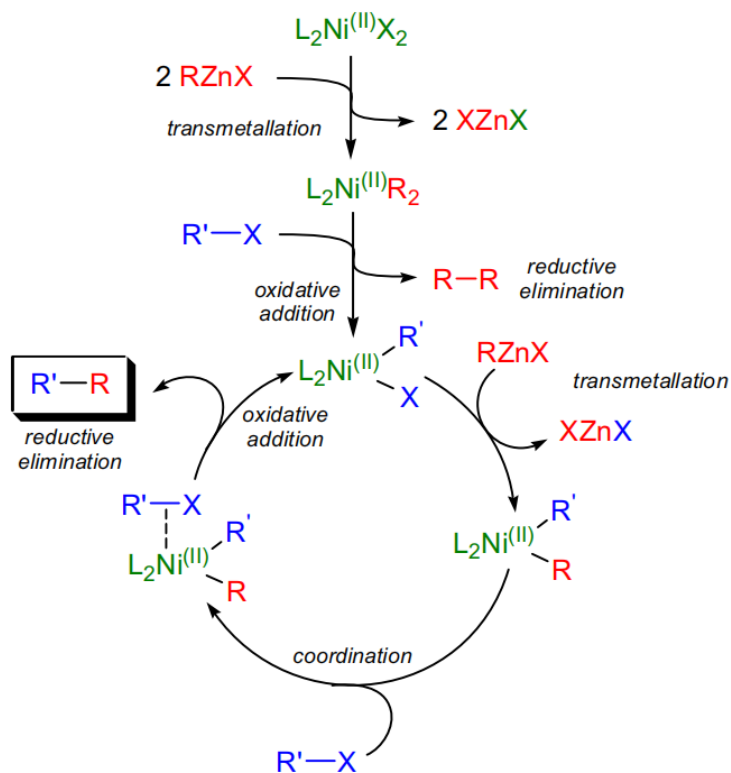
Angew. Chem. Int. Ed., **1993**, 32, 1068.

NEGISHI CROSS-COUPLING

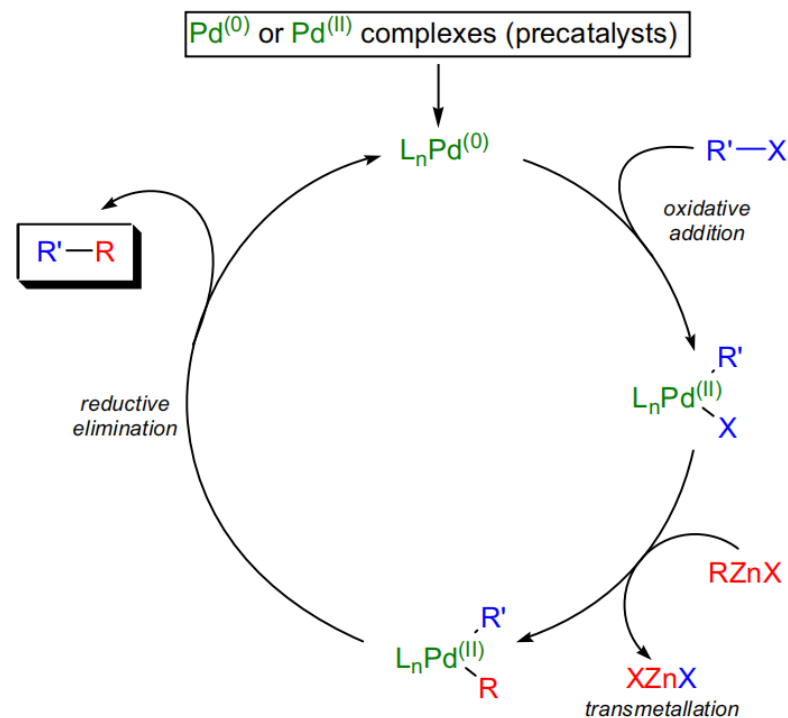
(References are on page 637)

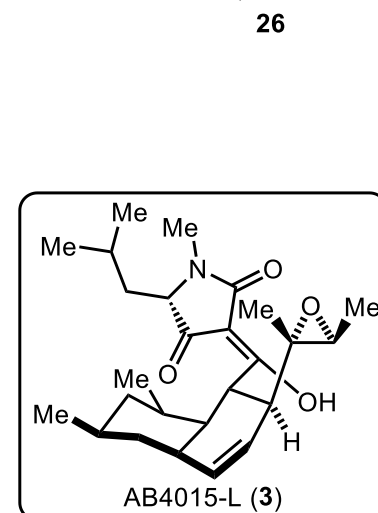
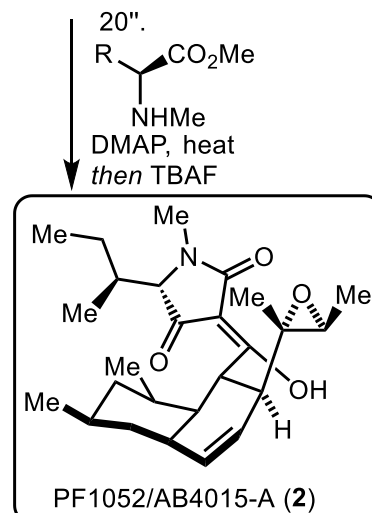
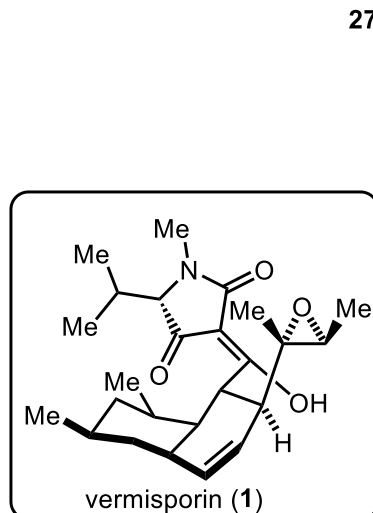
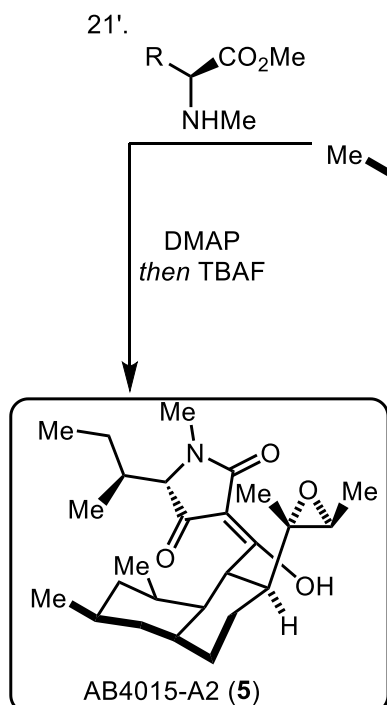
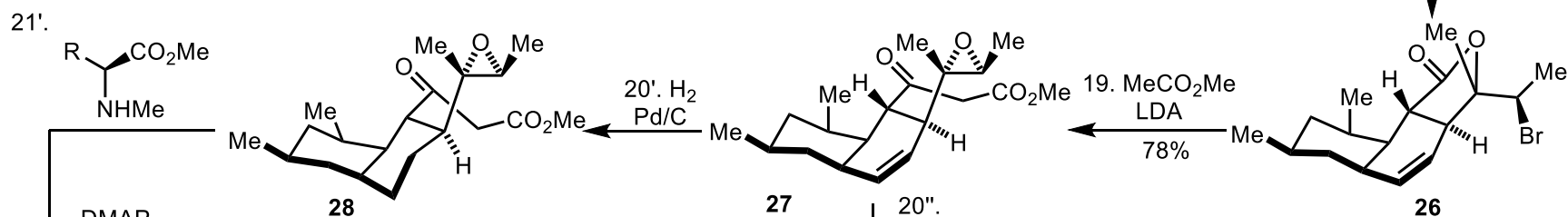
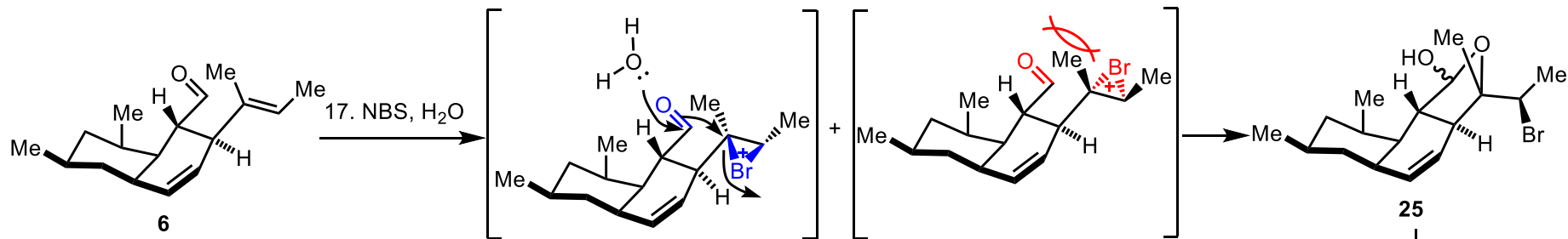
Mechanism: ¹⁰

Ni-catalyzed process:



Pd-catalyzed process:





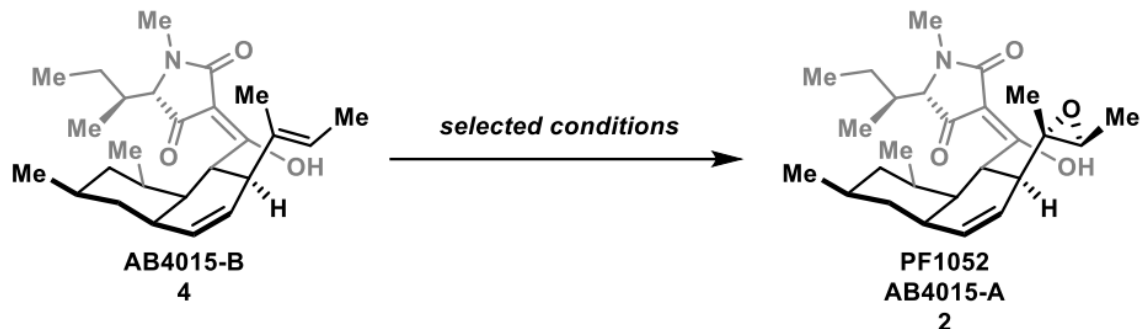
R = *s*-Bu, yield: 75% (2 steps)

R = *i*-Pr, yield: 74%

R = *s*-Bu, yield: 76%

R = *i*-Bu, yield: 74%

Table S2. Attempted epoxidation of AB4015-B (**4**) to obtain PF1052/AB4015-A (**2**)



Entry	Condition	Solvent	Temp.	Result
1	<i>m</i> -CPBA	DCM	0 °C	no desired product
2	<i>m</i> -CPBA, NaHCO ₃	DCM	0 °C	no desired product
3	TBHP, VO(acac) ₂	DCM	0 °C to rt.	decomposition
4	TBHP, Ti(O ^{<i>i</i>} Pr) ₄	DCM	0 °C to rt.	decomposition
5	DMDO	acetone	-78 °C to 0 °C	decomposition
6	Oxone [®] , NaHCO ₃	acetone/H ₂ O	0 °C to rt.	complex mixture
7	Oxone [®] , NaHCO ₃	MeCN/ H ₂ O	0 °C to rt.	complex mixture
	18-crown-6			
8 ^[1]	(-)-Shi's ketone Shi's epoxidation	DMM/MeCN/H ₂ O	-10 °C	complex mixture
9 ^[2]	(+)-Shi's ketone Shi's epoxidation	DMM/MeCN/H ₂ O	-10 °C	complex mixture

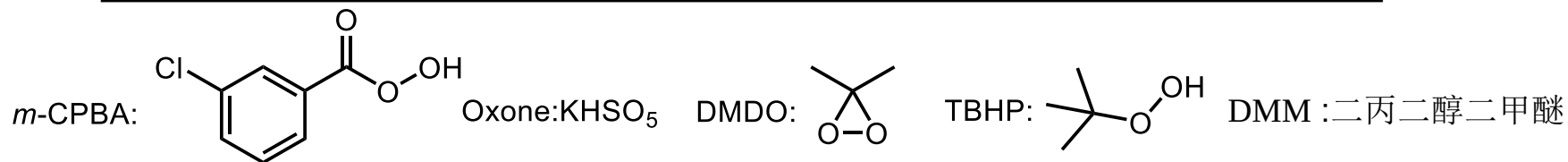
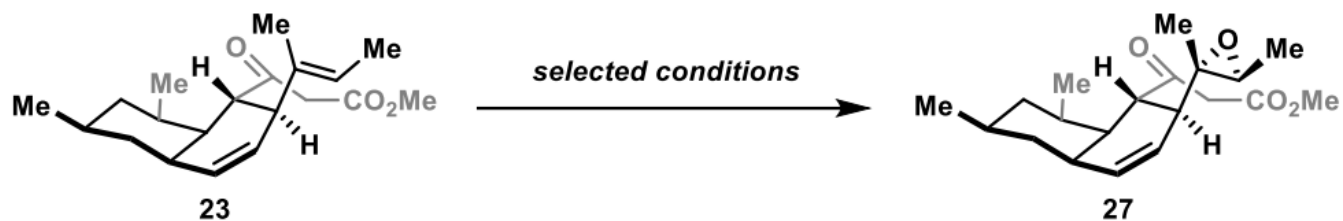


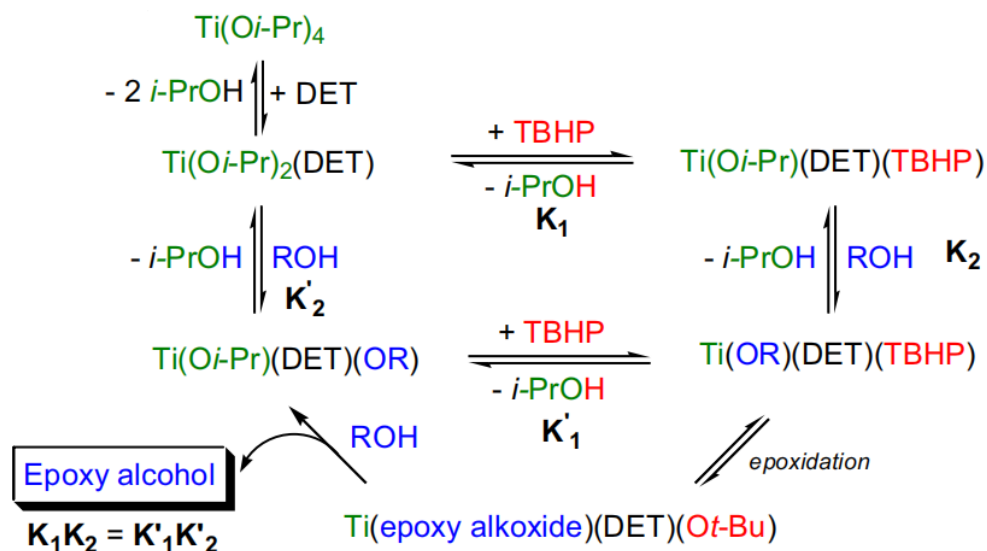
Table S3. Attempted epoxidation of compound **23** to obtain compound **27**



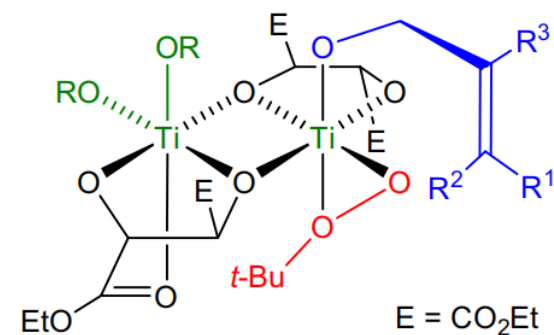
Entry	Condition	Solvent	Temp.	Result
1	<i>m</i> -CPBA	DCM	0 °C	no desired product
2	<i>m</i> -CPBA, NaHCO ₃	DCM	0 °C	no desired product
3	TBHP, VO(acac) ₂	DCM	0 °C to rt.	no reaction
4	DMDO	acetone	-78 °C to 0 °C	complex mixture
5	Oxone [®] , NaHCO ₃	acetone/H ₂ O	0 °C to rt.	complex mixture

SHARPLESS ASYMMETRIC EPOXIDATION

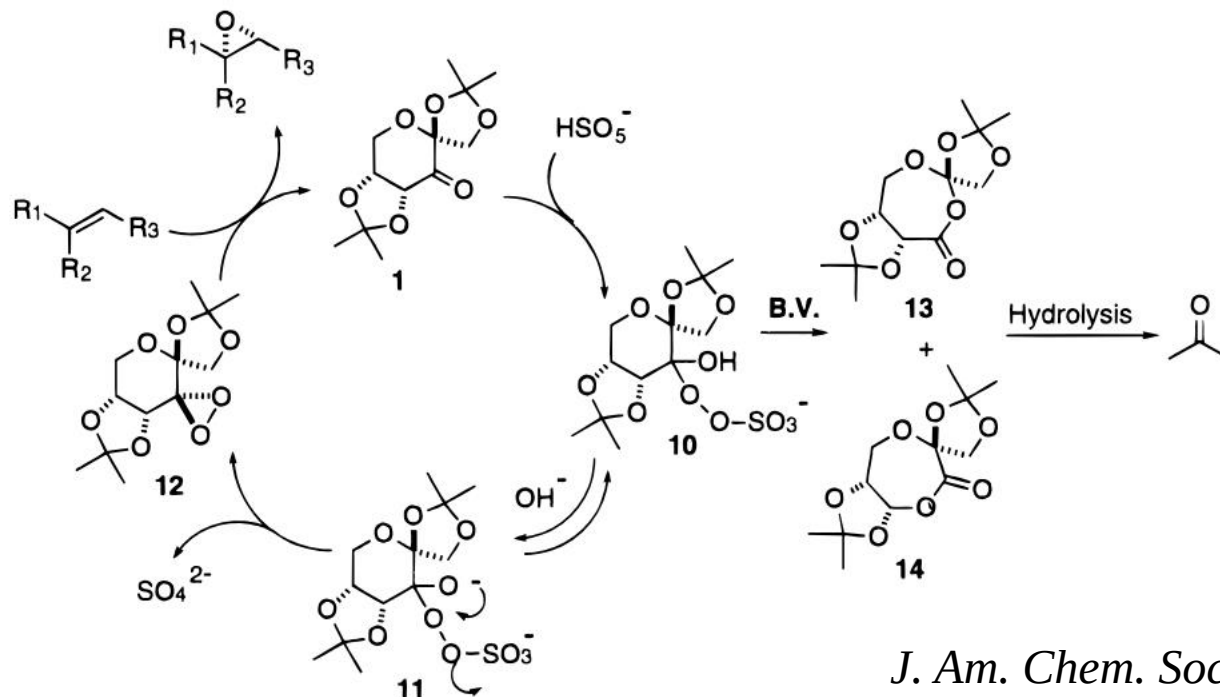
(References are on page 675)



Transition state of epoxidation:

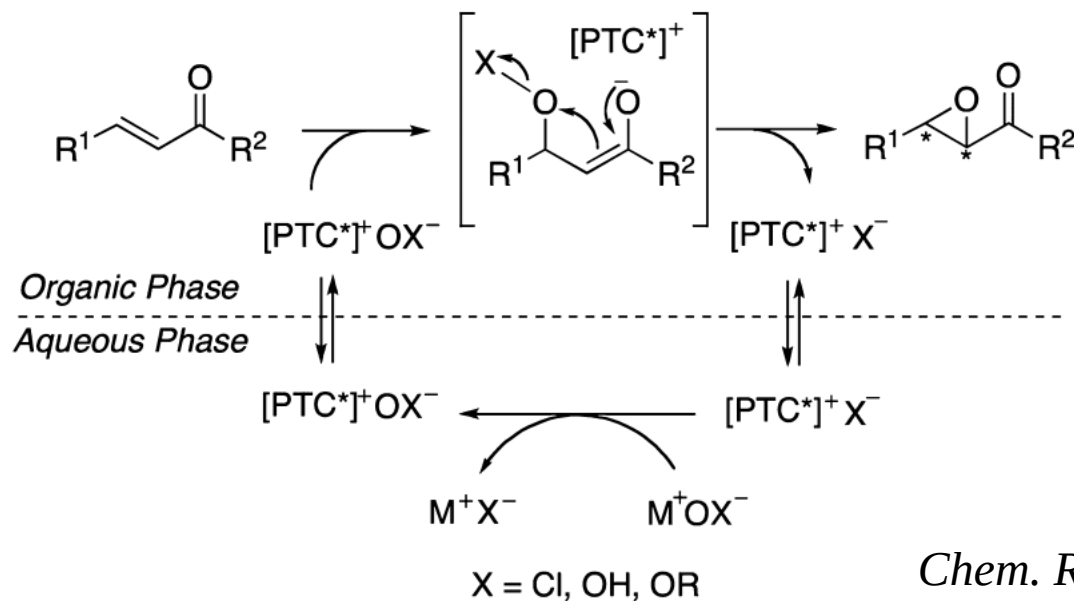


$$\text{Rate} = \frac{[\text{Ti(O}i\text{-Pr)}_2(\text{DET})][\text{TBHP}][\text{ROH}]}{[i\text{-PrOH}]^2}$$



J. Am. Chem. Soc., **1996**, *118*, 9806.

J. Am. Chem. Soc., **1997**, *119*, 11224.



Chem. Rev., **2014**, *114*, 8199.